Greg Denbeaux

List of Publications by Year
in descending order

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21 papers	263 citations	1040056 9 h-index	940533 16 g-index
21 all docs	21 docs citations	21 times ranked	178 citing authors

#	Article	IF	Citations
1	EUV Photochemistry of Î±-Substituted Antimony Carboxylate Complexes. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2021, 34, 81-86.	0.3	0
2	Isotopic Labeling Studies of EUV Photoresists Containing Antimony. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 233-242.	0.3	2
3	Mechanisms of EUV exposure: electrons and holes. , 2017, , .		8
4	Antimony photoresists for EUV lithography: mechanistic studies. Proceedings of SPIE, 2017, , .	0.8	6
5	Reactivity of metal-oxalate EUV resists as a function of the central metal. Proceedings of SPIE, 2017, , .	0.8	8
6	Analytical techniques for mechanistic characterization of EUV photoresists. Proceedings of SPIE, 2017, , .	0.8	6
7	EUV Mechanistic Studies of Antimony Resists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2017, 30, 121-131.	0.3	11
8	What We Donâ€™t Know About EUV Exposure Mechanisms. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2017, 30, 113-120.	0.3	19
9	Acid Generation Efficiency of EUV PAGs via Low Energy Electron Exposure. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2016, 29, 453-458.	0.3	18
10	Energy deposition and charging in EUV lithography: Monte Carlo studies. , 2016, , .		1
11	Cross sections of EUV PAGs: influence of concentration, electron energy, and structure. , 2016, , .		3
12	Cross sections of photoacid generators at low electron energies. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2015, 33, 06FH01.	1.2	11
13	Studying thickness loss in extreme ultraviolet resists due to electron beam exposure using experiment and modeling. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2015, 14, 043502.	0.9	7
14	Electron Penetration Depths in EUV Photoresists. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2014, 27, 611-615.	0.3	13
15	Secondary Electrons in EUV Lithography. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2013, 26, 625-634.	0.3	53
16	Resolution, Line-Edge Roughness, Sensitivity Tradeoff, and Quantum Yield of High Photo Acid Generator Resists for Extreme Ultraviolet Lithography. Japanese Journal of Applied Physics, 2011, 50, 036504.	1.5	31
17	Resolution, Line-Edge Roughness, Sensitivity Tradeoff, and Quantum Yield of High Photo Acid Generator Resists for Extreme Ultraviolet Lithography. Japanese Journal of Applied Physics, 2011, 50, 036504.	1.5	25
18	RLS tradeoff vs. quantum yield of high PAG EUV resists. , 2009, , .		13

#	Article	IF	Citations
19	Magnetization reversal study of CoCrPt alloy thin films on a nanogranular-length scale using magnetic transmission soft x-ray microscopy. Applied Physics Letters, 2003, 83, 4589-4591.	3.3	21
20	Imaging magnetic microstructures of with soft X-ray microscopies. Transactions of the Magnetics Society of Japan, 2002, 2, 234-237.	0.5	1
21	Spectromicroscopy at the XM-1. AIP Conference Proceedings, 2000, , .	0.4	6